| Notice of References Cited | Application/Control No. 09/901,917 | Applicant(s)/Patent Under Reexamination WALKER ET AL. | |
|---|---|---|---|
| | Examiner Toniae M Thomas | Art Unit 2822 | Page 1 of 1 |

**U.S. PATENT DOCUMENTS**

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Name | Classification |
|---|---|---|---|---|---|
| | A | US-4,843,025 B1 | 06-1989 | Morita | 438/388 |
| | B | US-4,918,499 B1 | 04-1990 | Matsutani et al. | 257/304 |
| | C | US-5,343,354 B1 | 08-1994 | Lee et al. | 361/322 |
| | D | US-5,346,845 B1 | 09-1994 | Jun | 438/244 |
| | E | US-6,114,216 B1 | 09-2000 | Yieh et al. | 438/424 |
| | F | US- | | | |
| | G | US- | | | |
| | H | US- | | | |
| | I | US- | | | |
| | J | US- | | | |
| | K | US- | | | |
| | L | US- | | | |
| | M | US- | | | |

**FOREIGN PATENT DOCUMENTS**

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Country | Name | Classification |
|---|---|---|---|---|---|---|
| | N | JP 63-001052 A | 01-1988 | JP | Kimura et al. | H01L 027/10 |
| | O | | | | | |
| | P | | | | | |
| | Q | | | | | |
| | R | | | | | |
| | S | | | | | |
| | T | | | | | |

**NON-PATENT DOCUMENTS**

| * | | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages) |
|---|---|---|
| | U | ~~Wolf et al., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films", Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, pages 181-182.~~ |
| | V | Wolf et al., "Semiconductor Memory Process Integration", Silicon Processing for the VLSI Era - Vol. 2: Process Integration, Lattice Press, 1990, page 602. |
| | W | Wolf et al., "Isolation Technologies for Integrated Circuits", Silicon Processing for the VLSI Era - Vol. 2: Process Integration, Lattice Press, 1990, page 48. |
| | X | Wolf et al., "Hot Carrier-Resistant Processing and Device Structures", Silicon Processing for the VLSI Era - Vol. 3: The Submicron MOSFET, Lattice Press, 1995, pages 634-636. |

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.